

Appendix B

Because CCVD generally uses solutions, a significant advantage of this technology is that it allows rapid and simple changes in dopants and stoichiometries which eases deposition of complex films. The CCVD technique generally uses inexpensive, soluble precursors. The Nanomiser™ as described in co-pending U.S. Patent Applications No. 08/691,853, filed 8/2/96, (now U.S. Patent No. 5,997,956), and U.S. Patent Applications Nos. 09/293,867, (now abandoned) 09/293,028 (now abandoned) and 09/293,030, (now U.S. Patent No. 6,132,653) all filed 4/16/99 as divisionals of U.S. Patent Application No. 08/691,853, breaks the liquid into micron or even sub-micron sized droplets. These patent applications are all owned by the assignee of the present invention and are hereby incorporated by reference. In addition, precursor vapor pressures generally do not play a role in CCVD because the dissolution process provides the energy for the creation of the necessary ionic constituents. By adjusting solution concentrations and constituents, a wide range of stoichiometries can be deposited quickly and easily. Additionally, the CCVD process allows both chemical composition and physical structure of the deposited film to be tailored to the requirements of the specific application.